Special Issue

New Trends in Chemical Looping

Message from the Guest Editors

This Special Issue on “New Trends in Chemical Looping” seeks high-quality works covering the latest progress in low-carbon and clean production from the chemical-looping concept. Topics include but are not limited to:

- Innovative oxygen-carrying or multifunctional materials;
- Novel concept or application of the chemical-looping process;
- New solutions to the issues on chemical looping, e.g., agglomeration, attrition, etc.;
- New demonstration or reactor design of the chemical-looping process.

Guest Editors

Dr. Guicai Liu

Dr. Shiwen Fang

Dr. Xudong Wang

Dr. Jianjun Cai

Deadline for manuscript submissions

closed (20 August 2024)

Processes

an Open Access Journal
by MDPI

Impact Factor 2.8
CiteScore 5.5

mdpi.com/si/130477

Processes
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34
processes@mdpi.com

mdpi.com/journal/processes

Processes

an Open Access Journal
by MDPI

Impact Factor 2.8
CiteScore 5.5

mdpi.com/journal/processes

MDPI

About the Journal

Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

Prof. Dr. Giancarlo Cravotto
Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

Author Benefits

Open Access:

free for readers, with article processing charges (APC) paid by authors or their institutions.

High Visibility:

indexed within Scopus, SCIE (Web of Science), Ei Compendex, Inspec, AGRIS, and other databases.

Journal Rank:

CiteScore - Q2 (Chemical Engineering (miscellaneous))